



JETLIGHT 50

Entry Level RTP System

Versatile, compact size and cost effective, software controlled bench-top type RTP tool, specifically designed to meet requirements of R&D laboratories and small-scale production units



POSSIBLE PROCESSES :

_Rapid thermal annealing (RTA), Oxidation (RTO)
Nitridation (RTN), Diffusion (RTD)
_Implant monitoring
_Cystrallization, Carbonization
_Contact alloying
_Stress relaxation

RTP MODULE CHARACTERISTICS :

_Quartz tube chamber _6 IR lamps heating system with tangential fan cooling _Water-cooled reflector and flanges _16kW heating power and 3x400V+N+Gnd supply _Temperature from Ambiant to 1000°C _Ramp rate from 1°C/sec to 50°C/sec _Digital PID température control through TC K type

_Dimensions mm (LxWxH) : 600x685x535

KEY FEATURES :

- _Software-controlled (PLC and PC)
- _Hot-wall (quartz tube) chamber design
- _2 gas lines with manual ball flow meter control
- _Substrate size up to 50mm diameter
- _Quartz tubes substrate holder
- _Atmospheric and vacuum process capabilities
- _Microprocessor-based thyristor technology



MAIN STRENGHTS :

- _Low cost versatile tool for a large range of applications, ideal for research labs
- _Easy control of temperature profiles to adjust the process
- _Quartz support for other sizes of substrate on request
- _Process at atmospheric pressure or under vacuum
- _Standard equipement allowing short delivery time